

	Hits	Search Text	DBs	Time Stamp
1	9	(chamber and substrate and titanium and ((physical adj vapor adj deposition) PVD) and hydrogen).clm.	US-PGPUB	2005/11/23 17:15
2	28	(chamber and substrate and titanium and sputter\$3 and hydrogen).clm.	US-PGPUB	2005/11/23 17:15
3	8	(chamber and substrate and titanium and ((physical adj vapor adj deposition) PVD) and hydrogen and plasma).clm.	US-PGPUB	2005/11/23 17:16
4	24	(chamber and substrate and titanium and sputter\$3 and hydrogen and gas).clm.	US-PGPUB	2005/11/23 17:15
5	2	(chamber with substrate and titanium with ((physical adj vapor adj deposition) PVD) and hydrogen).clm.	US-PGPUB	2005/11/23 17:15
6	5	(chamber with substrate and titanium with sputter\$3 and hydrogen).clm.	US-PGPUB	2005/11/23 17:16
7	5	(chamber with substrate and titanium with sputter\$3 and hydrogen and gas).clm.	US-PGPUB	2005/11/23 17:16
8	2	(chamber with substrate and titanium with ((physical adj vapor adj deposition) PVD) and hydrogen and plasma).clm.	US-PGPUB	2005/11/23 17:16